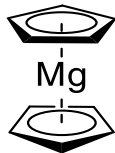


Catalog # 12-0500 Bis(cyclopentadienyl)magnesium (99.9+%-Mg)



Thermal Behavior:

- Melting point 176°C
- Boiling point 290°C
- Sublimation 160°C/0.1mm
- Vapor pressure 0.027 Torr/20°C, Diagram is available in [1]

Technical Notes:

1. ALD/CVD precursor and dopant for Mg thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
MgO	ALD	50°C	-	H ₂ O	100-400°C	2
	ALD	35°C	-	H ₂ O	80-350°C	3
	PEALD	50°C	-	^P L ₂ O ₂	300°C	4
MgAl ₂ O ₄	ALD	50°C	-	Me ₃ Al, H ₂ O	100-400°C	5
Zn _{1-x} Mg _x O	ALD	57°C	-	Et ₂ Zn, H ₂ O	105-180°C	6
Mg:GaN	CVD	-	-	Me ₃ Ga, NH ₃	920°C	7

References:

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7. [J. Appl. Phys. 2020, 128, 055301.](#)